

Title (en)

DEPOSITION REACTOR WITH INDUCTORS AND ELECTROMAGNETIC SHIELDS

Title (de)

ABSCHIEDUNGSREAKTOR MIT INDUKTOREN UND ELEKTROMAGNETISCHEN ABSCHIRMUNGEN

Title (fr)

RÉACTEUR DE DÉPÔT DOTÉ DE BOBINES D'INDUCTION ET DE BLINDAGES ÉLECTROMAGNÉTIQUES

Publication

**EP 3870734 A1 20210901 (EN)**

Application

**EP 19801977 A 20191024**

Priority

- IT 201800009819 A 20181026
- IB 2019059127 W 20191024

Abstract (en)

[origin: WO2020084563A1] The reactor (100) for deposition of layers of semiconductor material on substrates, comprises: a reaction chamber (110), a susceptor assembly (120) located inside the reaction chamber, and a heating system (130) adapted to heat the susceptor assembly by electromagnetic induction; the heating system (130) comprises a first (131) inductor and a second (132) inductor and a power supply (135) adapted to electrically feed the first and second inductors (131, 132) with alternating currents that are distinct and independent from one another; the reactor (100) further comprises a shielding assembly (140) adapted to limit electromagnetic coupling between the first and the second inductors (131, 132).

IPC 8 full level

**C23C 14/26** (2006.01); **C23C 16/46** (2006.01); **C30B 13/20** (2006.01); **C30B 13/30** (2006.01); **C30B 35/00** (2006.01); **H05B 6/44** (2006.01)

CPC (source: EP US)

**C23C 16/46** (2013.01 - EP US); **C30B 35/00** (2013.01 - EP); **H05B 6/105** (2013.01 - EP); **H05B 6/44** (2013.01 - EP US); **C30B 25/10** (2013.01 - US)

Citation (search report)

See references of WO 2020084563A1

Designated contracting state (EPC)

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Designated extension state (EPC)

BA ME

DOCDB simple family (publication)

**WO 2020084563 A1 20200430**; CN 112752864 A 20210504; CN 112752864 B 20240126; EP 3870734 A1 20210901; JP 2022504358 A 20220113; US 2022025519 A1 20220127

DOCDB simple family (application)

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